Application Number: <u>Unknown</u>
Filing Date: <u>Unknown</u>
First Named Inventor: <u>Richard A. Blanchard</u>
Group Art Unit: <u>Unknown</u>
Examiner Name: <u>Unknown</u>
Attorney Docket: <u>BLAN-9</u>

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37 CRF 1.98(b)	INF	INFORMATION DISCLOSURE STATEMENT BY APPLICANT										
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Examiner Signature								I .	Date Considered				

^{**}EXAMINER: Initial citation considered. Draw line through citation if no in conformance and not considered. Include copy of this form with next communication to application.